



Session Title:	[WeE1] Advanced Etching I
Session Date:	November 13 (Wed.), 2024
Session Time:	09:00-10:20
Session Room:	Room E (Sicily Room, 1F, Paradise Hotel Busan)
Session Chair:	Dr. Peter Ventzek (Tokyo Electron America Inc., USA)

[WeE1-1] [Invited] **09:00-09:30**

Challenges and Approaches in Advanced Patterning for Microelectronics

Chanmin Lee, Yeong-Shin Park, Youngsik Seo, and Jong Myeong Lee (Samsung Electronics Co., Ltd., Korea)

[WeE1-2] [Invited] **09:30-10:00**

Controlling Lateral Modification on Plasma Oxidation Using Optimizing Plasma Conditions during Isotropic Atomic Layer Etching

Ilyoung Kim, Taewan Kim, Seongkwang Lee, Hahnjoo Yoon, Sangman Park, and Yunsang Kim (SEMES, Korea)

[WeE1-3] **10:00-10:20**

Plasma-Enhanced Atomic Layer Etching of Titanium Nitride Using Surface Fluorination or Chlorination

Heeju Ha, Hyeongwu Lee, Minsung Jeon, and Heeyeop Chae (Sungkyunkwan Univ., Korea)